はんだ上がり欠陥

【原因、判断要点、发生工序】在 DFR 上夹杂毛发或 者不透明纤维、妨碍曝光而引起的。如果在 AWF 附 着毛发或者小纤维, 开路就会断续或者成为缺口(曝 光~ ET 工序)。

[Causes/processes involved/keys to judgment]

The open is caused by a hair or an opaque fibrous object present on the dry film blocking the exposure light. When the hair or the fibrous object is very fine or when they are on the phototool, they may cause intermittent opens or nicked lines. (Exposure and etching process)



【コメント】 顕微鏡倍率× 40 显微镜倍率 × 40

(Coments)
Magnification: X40



顕微鏡倍率×60 【注释】

显微镜倍率 × 60

[Coments]
Magnification: ×60

回路状断線/线路形状的开路 / Conductor-pattern-like open

【特徴】断線部の形状が、四角形に近い形で、欠陥 とは思えないシャープなもの。回路と見間違えられ るような形

【特征】开路部位的形状接近四方形,简直不像缺陷, 常常会错认为线路。

[Characteristics] The open portion is well defined to nearly square in shape that it does not look like a defect and often mistaken as a portion of conductor pattern.

【原因・判断ポイント・発生工程】完全に露光し不 透明化した長方形状DFR片等が、回路露光時のD FR上に介在し、露光が遮ぎられて出来たもの。複 数回路線に跨ることもある(露光焼付~ET工程)。

【原因、判断要点、发生工序】在 DFR 上夹杂着完全 曝光的不透明四方形的 DFR 碎片等,妨碍曝光而引 起的,有时横跨多条线路(曝光~ET工序)。

[Causes/processes involved/keys to judgment]

The defect is caused by opaque dry film debris that has been completely cured and is staying on the dry film before intendend photo-processing to block the exposure through the phototool.. Multiple conductors are often affected. (Exposure and etching process)

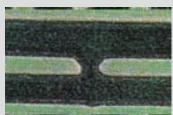


【コメント】 顕微鏡倍率× 50

显微镜倍率 × 50

[Coments]

Magnification: X50



顕微鏡倍率×50

显微镜倍率 × 50

[Coments] Magnification: ×50